

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Hada et al.
Appl. No. : 10/557,694
Filed : November 22, 2005
For : RESIN FOR PHOTORESIST
COMPOSITION, PHOTORESIST
COMPOSITION AND METHOD
FOR FORMING RESIST
PATTERN
Examiner : Kelly, C.
Group Art Unit : 1752

PRELIMINARY AMENDMENT

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Preliminary to examination on the merits, please amend the above-captioned U.S. National Phase Application as follows:

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims are reflected in the listing of claims which begins on page 3 of this paper.

Remarks/Arguments begin on page 7 of this paper.